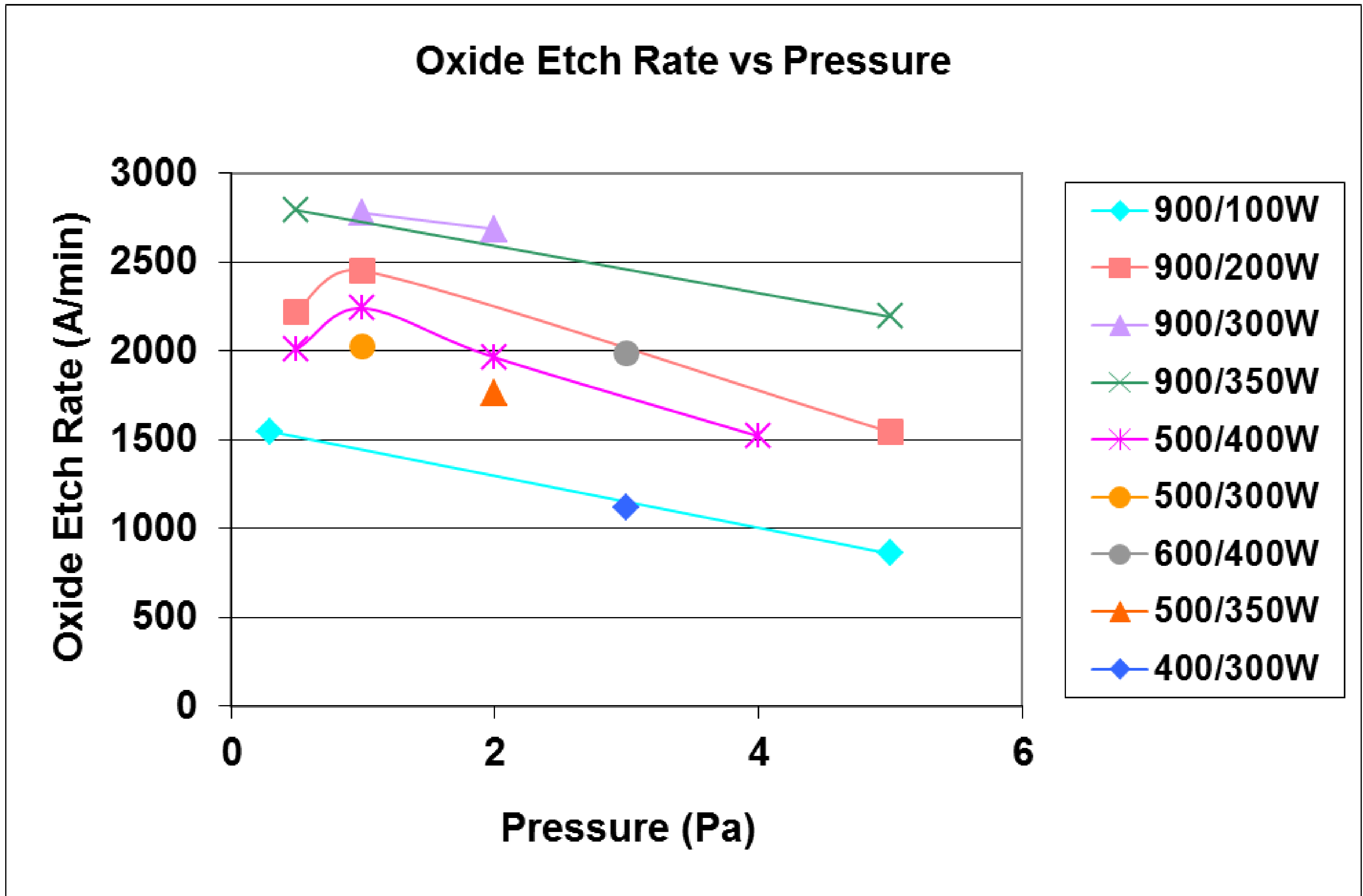
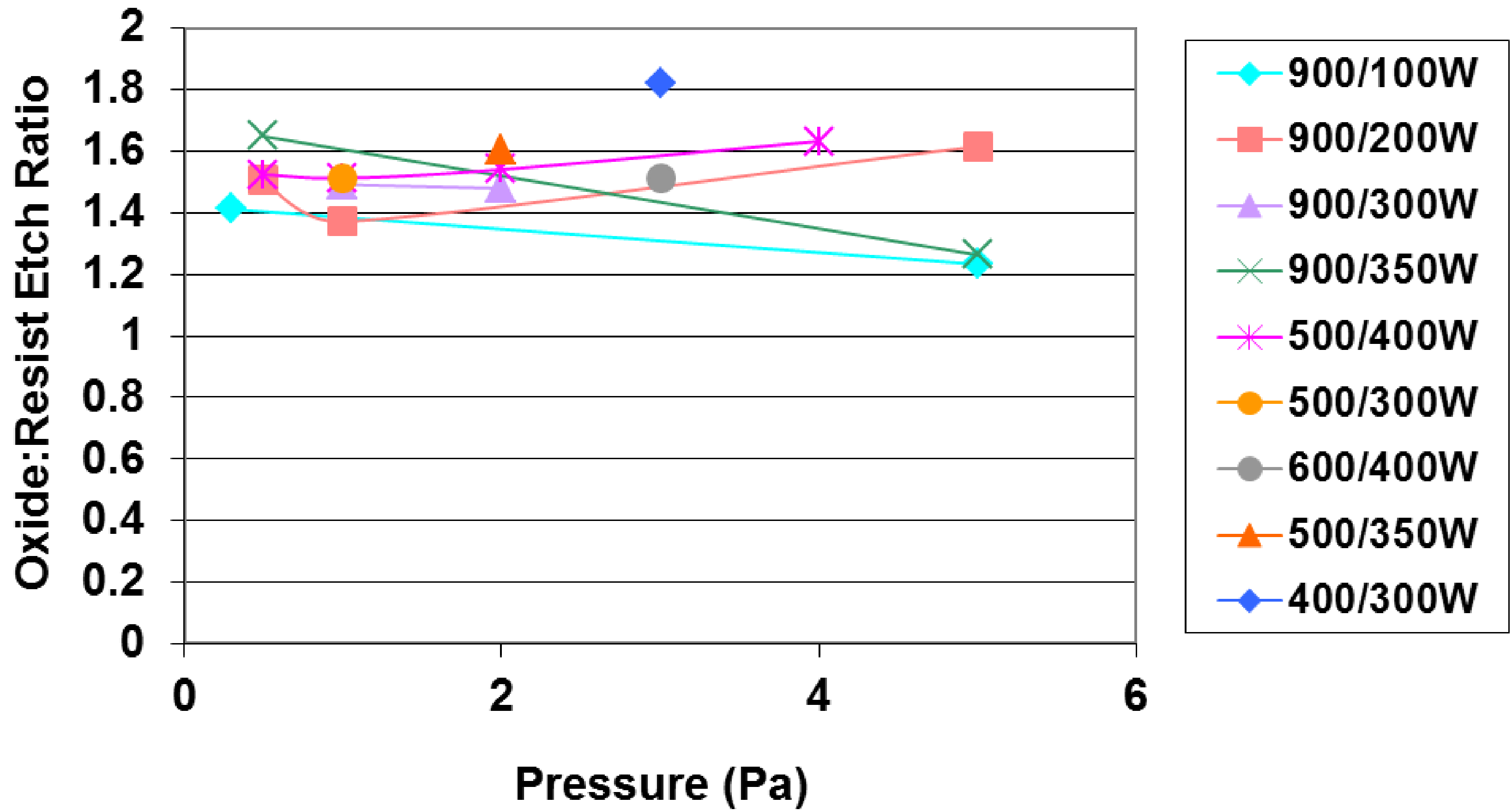
Panasonic 1 Process Variations for CHF3-Based SiO2 etching

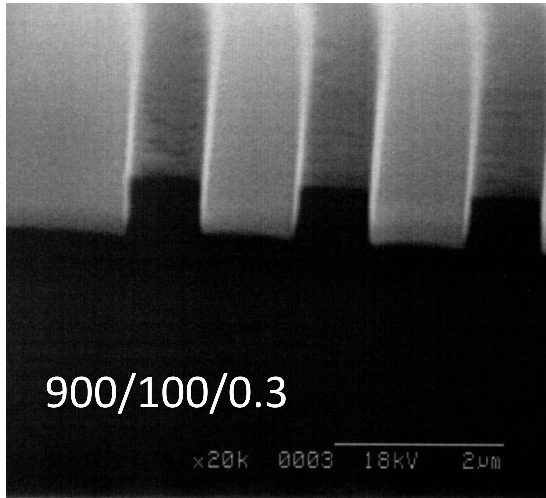
Based on Recipe 118, SiOVert, CHF_3 flow = 40sccm

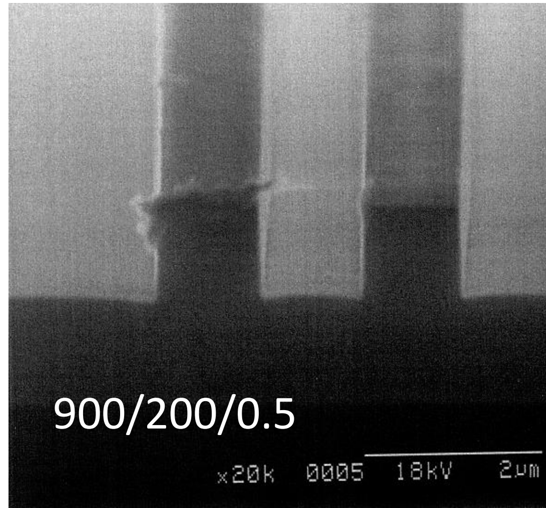


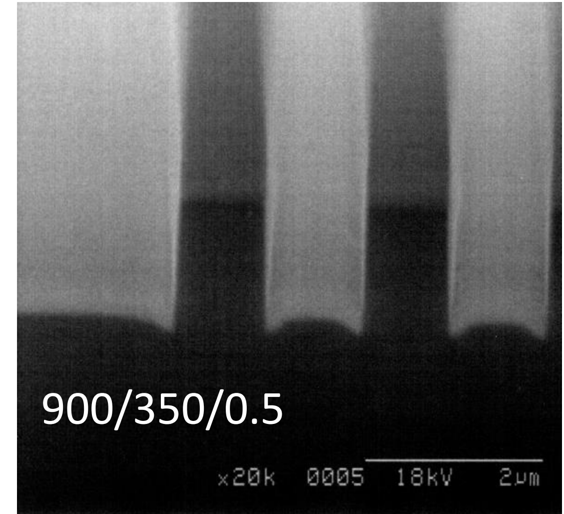
Based on Recipe 118, SiOVert, CHF_3 flow = 40sccm

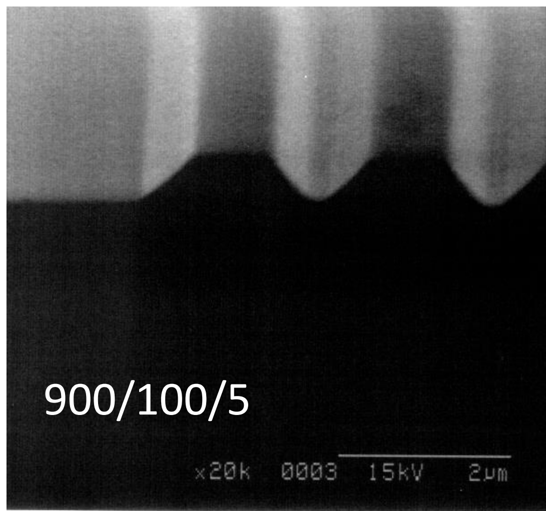


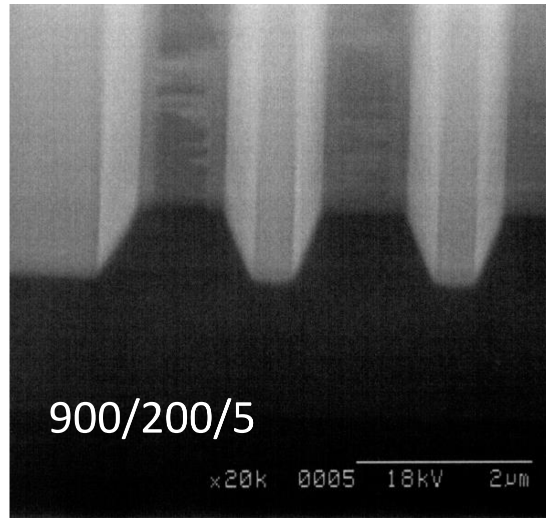
Based on Recipe 118, SiOVert, CHF_3 flow = 40sccm

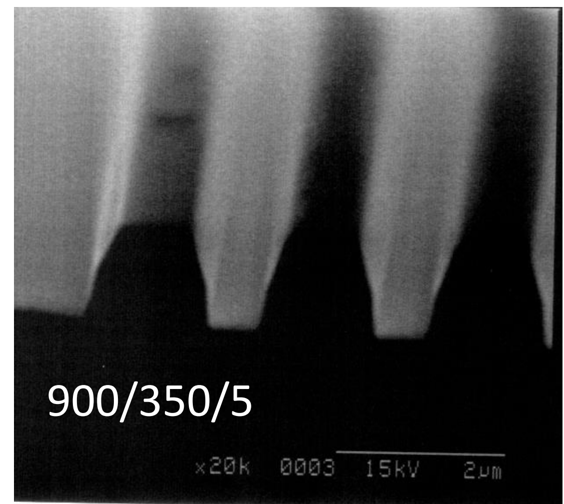












ICP/Bias/Pressure